

ABSTRACT

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The present invention provides a negative photosensitive resin composition comprising (A) a

5 photocurable resin having a photosensitive group or groups crosslinkable by light irradiation, (B) a photoacid generator and (C) a photosensitizer which is a benzopyran condensed ring compound capable of increasing

10 photosensitivity to visible light with a wavelength of 480 nm or more,

a negative photosensitive dry film prepared by applying the photosensitive resin composition to a surface of support film, followed by drying, to form a photosensitive resin layer, and

15 a method of forming a pattern using the resin composition or the dry film.